

I.N.F.M.

Epitaxial SiC detectors : Charge collection efficiency and photoluminescence characterisation

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OUTLINE OF THE TALK

- Samples description
- CV, IV electrical characterization
- charge collection efficiency (cce) characterization under exposure to a ^{241}Am alpha source
- charge collection distance measurements under exposure to a MIP from a ^{90}Sr b source
- Near band-edge recombination as a probe of crystalline quality

Schematic of the IKZ samples

circular Schottky contact

Ni_2Si f = 1.5 mm

n⁻, 4H – SiC, 40 ± 2 mm
epitaxial 4H-SiC

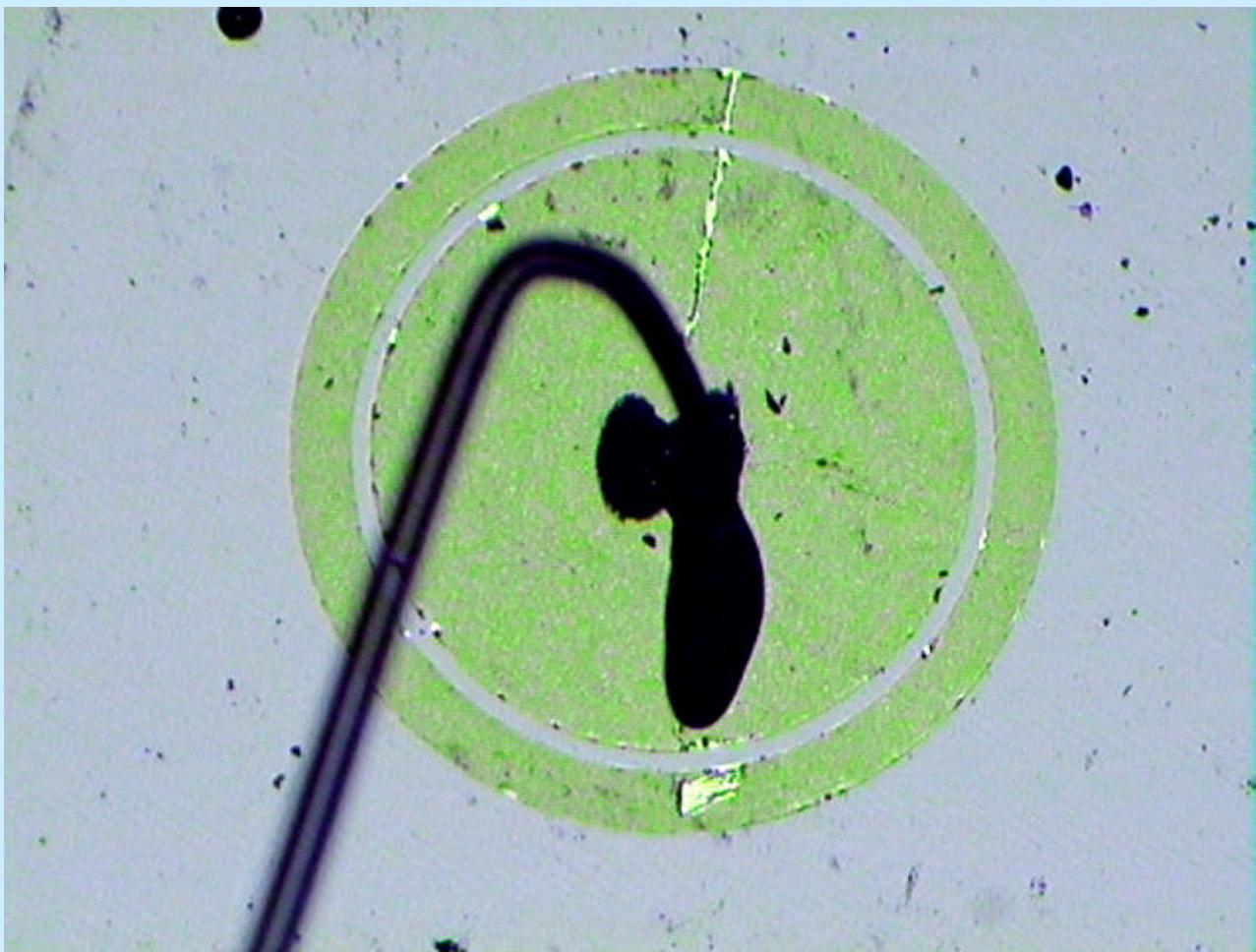
n⁺, 4H – SiC, 360 nm

substrate

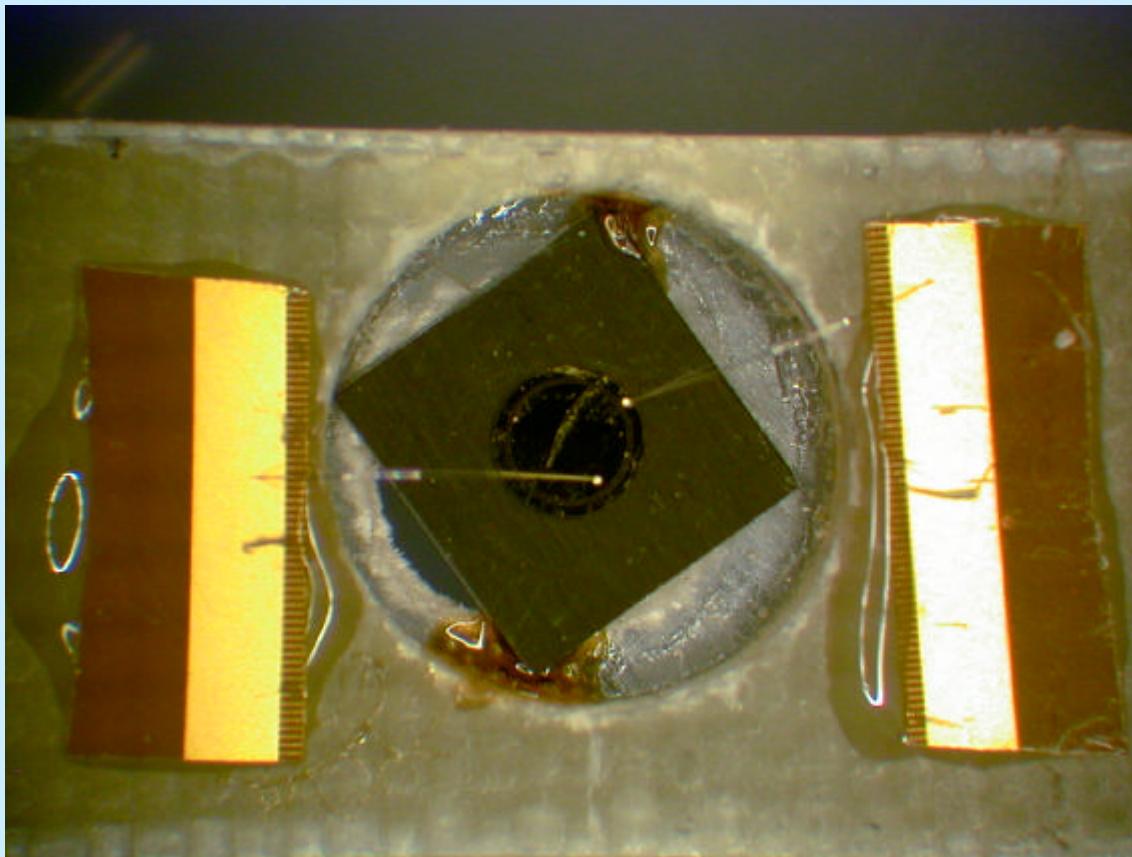
Ohmic contact -
Ti/Pt/Au

- Device produced by Alenia Marconi
- Optical measurement of thickness
- Ni₂Si metallisation: better adhesion, higher reproducibility

DEVICE UNDER TEST



DEVICE UNDER TEST

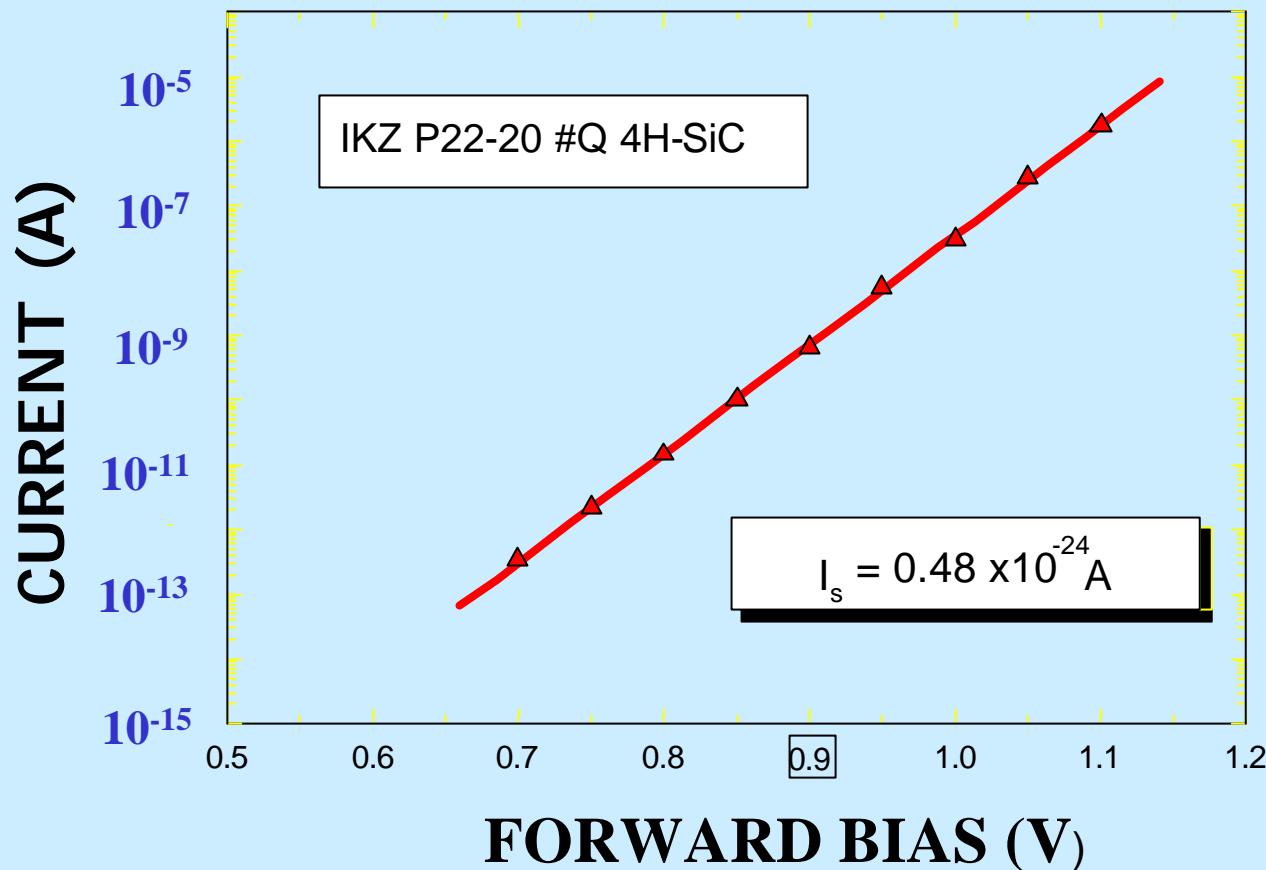


**Sample #Q
exhibits a very
low reverse
current and its
ideality factor is
very close to one**

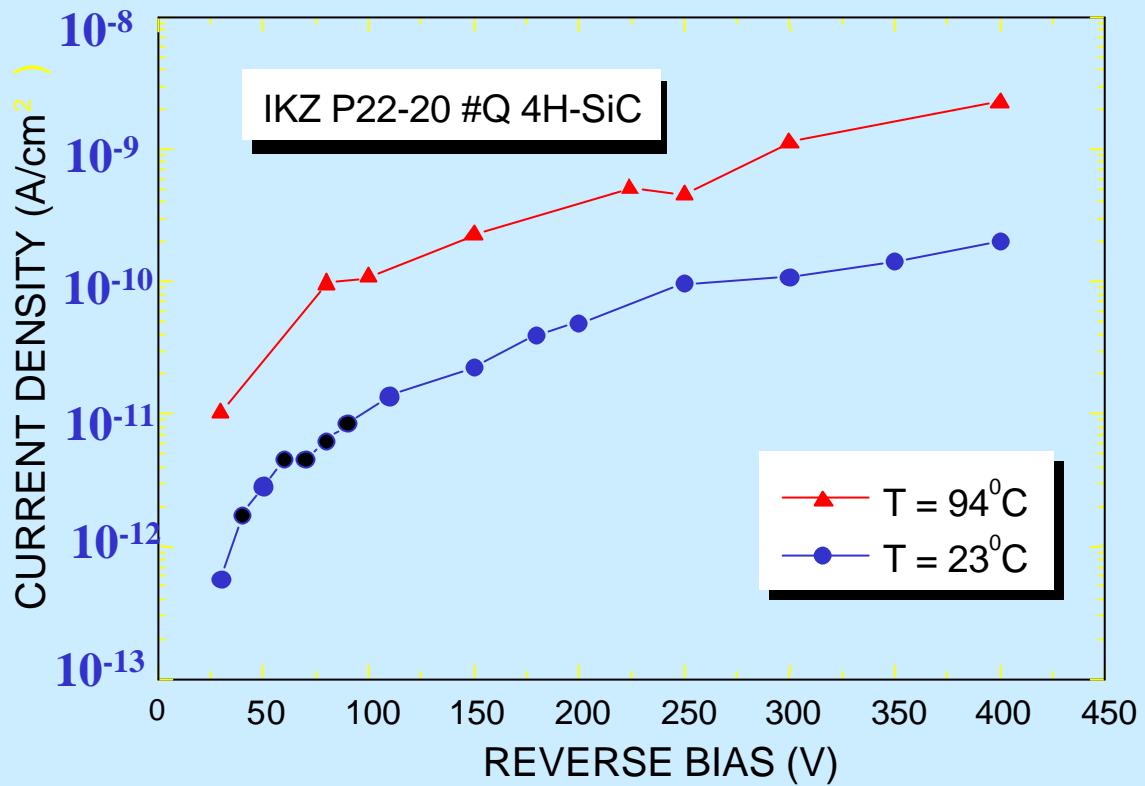
SAMPLE	N _{eff} [10 ¹³ /cm ³]	qV _{bi} [eV]	n	REVERSE-CURRENT (at 300 V) [A]
P	6,25	1.55	1.17	High (4.0 x 10 ⁻⁹)
G	4.73	1.49	1.13	Medium (8.6 x 10 ⁻¹¹)
E	5.68	1.51	1.13	Medium (1.0 x 10 ⁻¹⁰)
C	7.74	1.53	1.04	Very low (4.0 x 10 ⁻¹²)
O	7.66	1.60	1.54	Very high (2.8 x 10 ⁻⁶)
D	6.80	1.53	1.13	Medium (5.7 x 10 ⁻¹⁰)
Q	4.73	1.56	1.00	Very low (2.0 x 10 ⁻¹²)
M	6.82	1.59	1.07	Very high (> 10 ⁻⁸)
H	8.13	1.59	1.07	Medium (4.37 x 10 ⁻¹⁰)

For extrapolation by forward IV measurements:

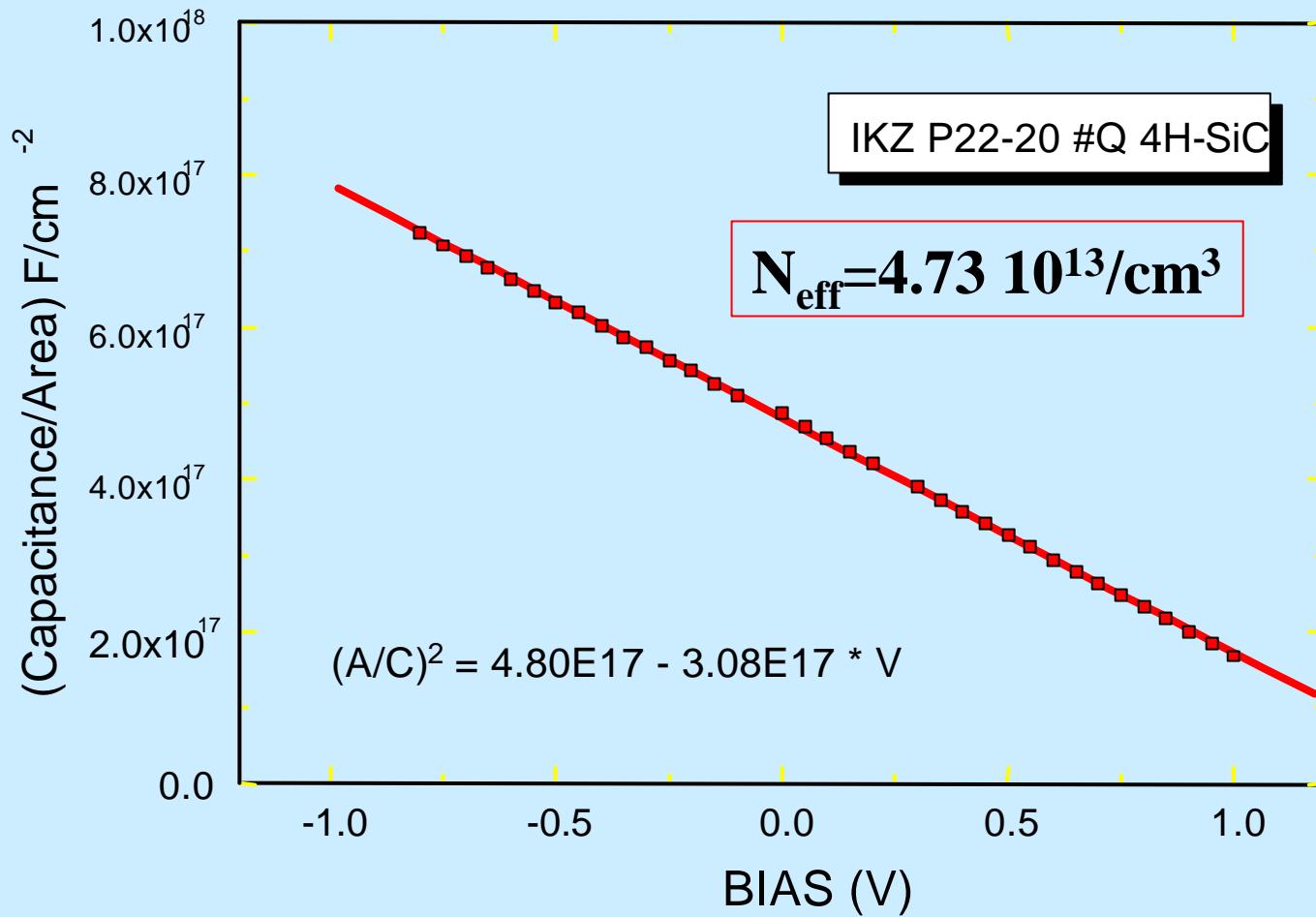
$$I_0 = 0.48 \times 10^{-24} \text{ A} \quad n(\text{ideality factor}) = 1 \quad F_{B0} \text{barrier height} = 1.77 \text{ eV}$$

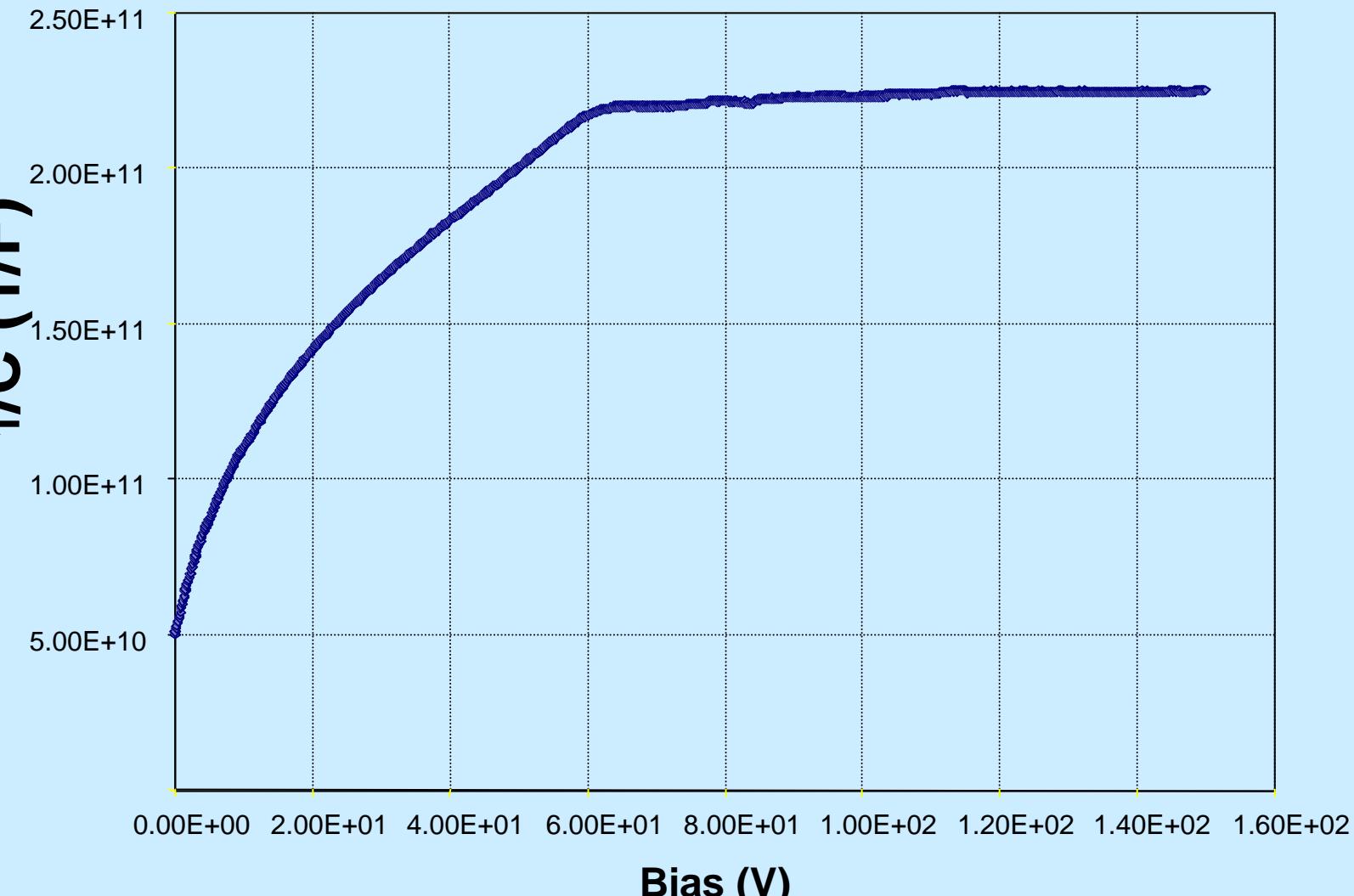


Inverse J_s measurements: low increment in dark current with increasing temperature



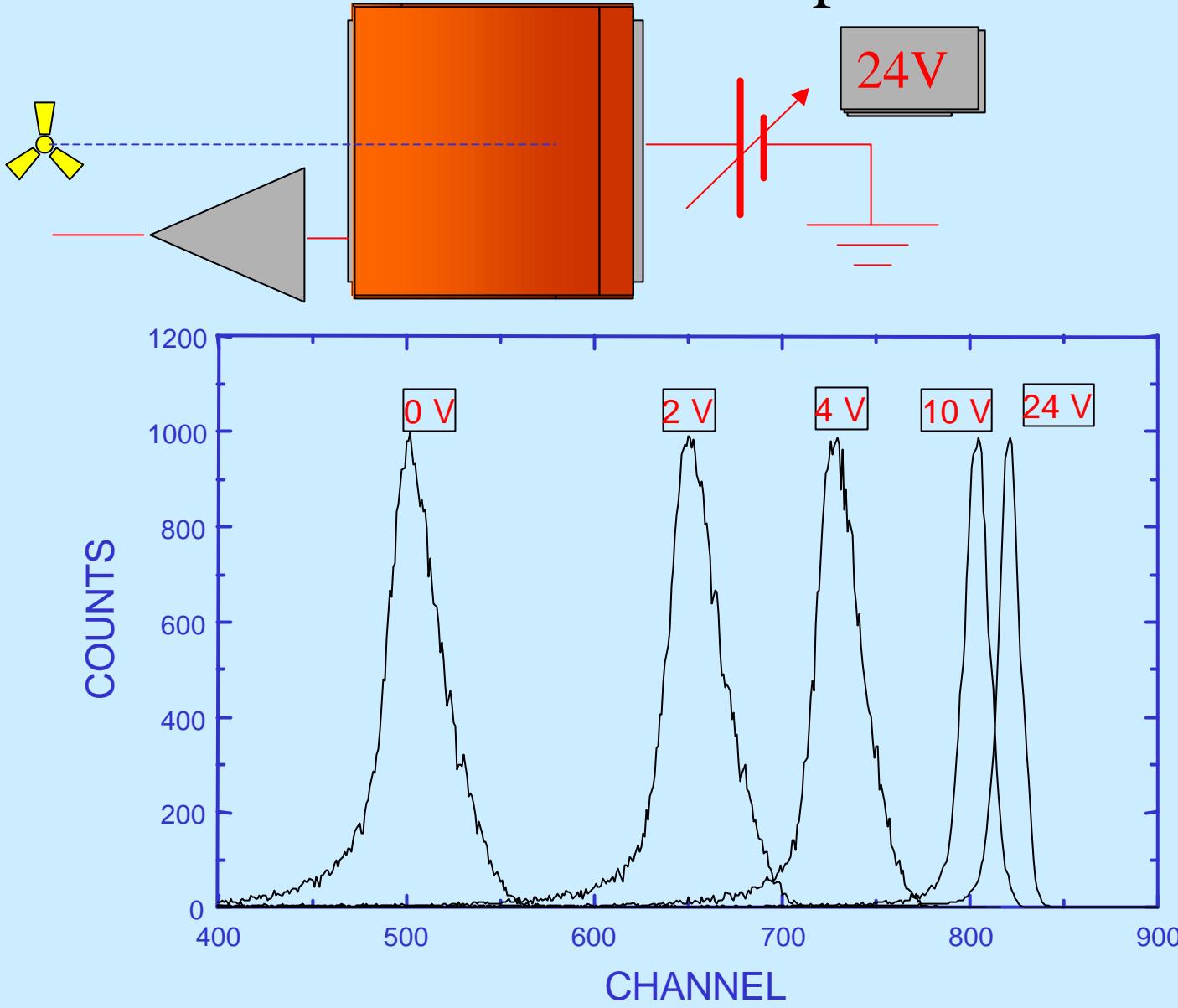
C-V measurements



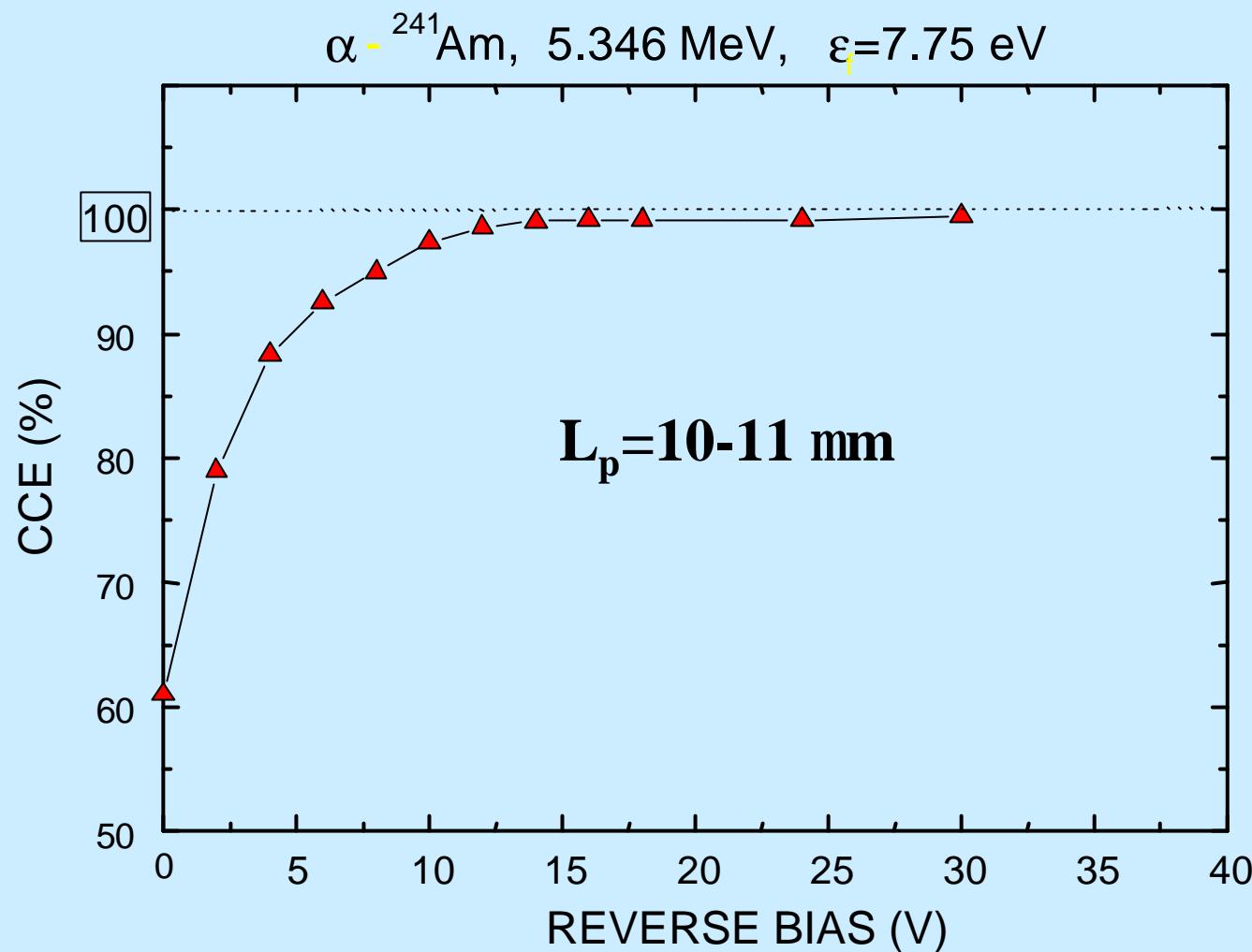


$$V_{dep} = 60 \text{ V}$$

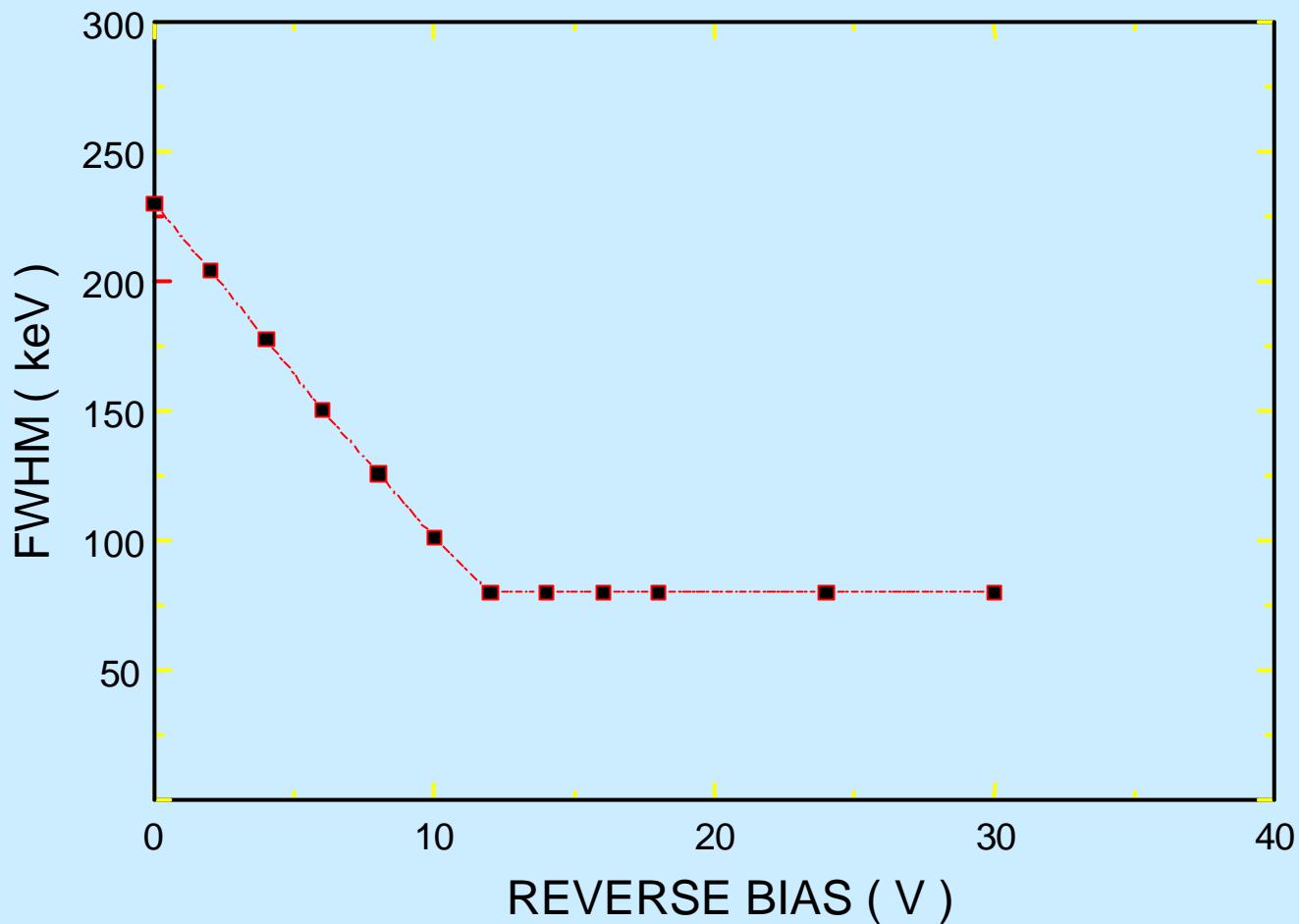
CCE under 5.346MeV α particle irradiation



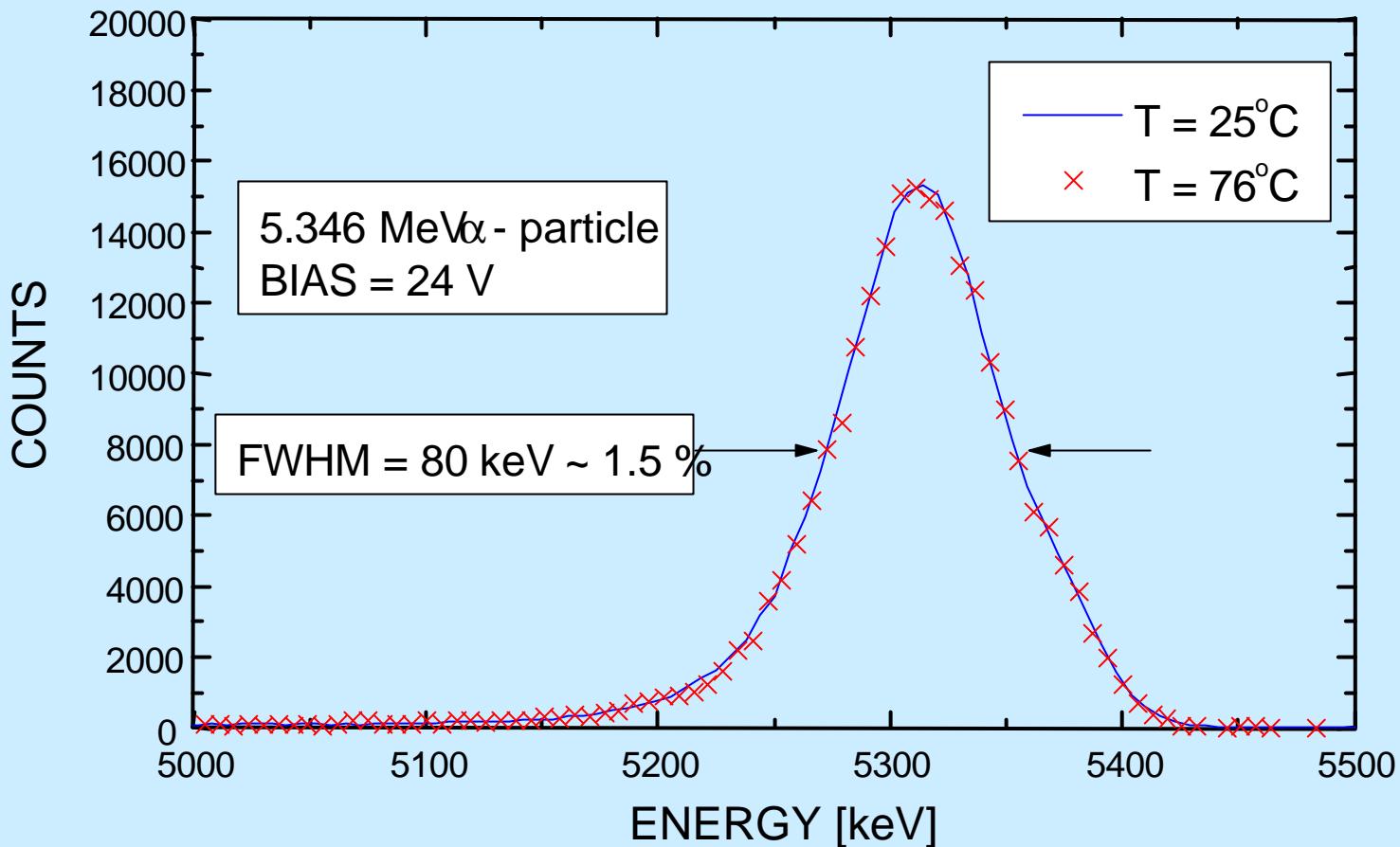
Saturation at 15÷20 V bias, depletion $\approx 20\mu\text{m}$



Saturation of FWHM above 10V



No relevant dependance of CEE Spectrum on temperature



Measure of collection efficiency of b MIP

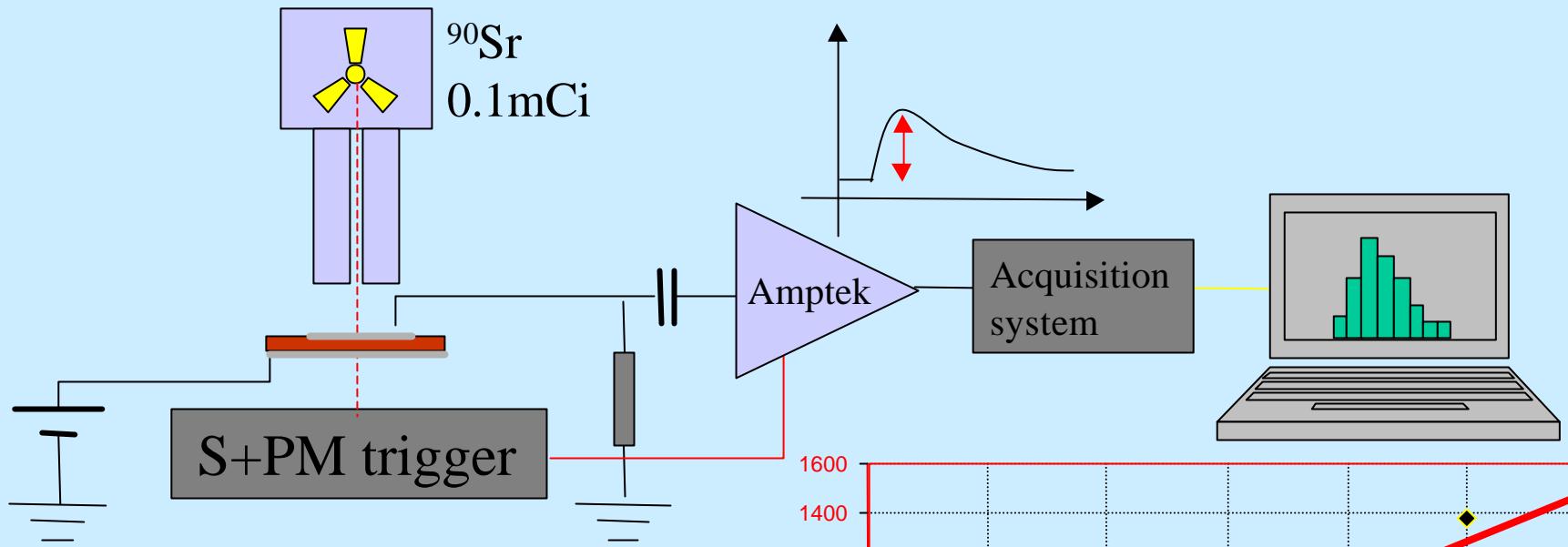
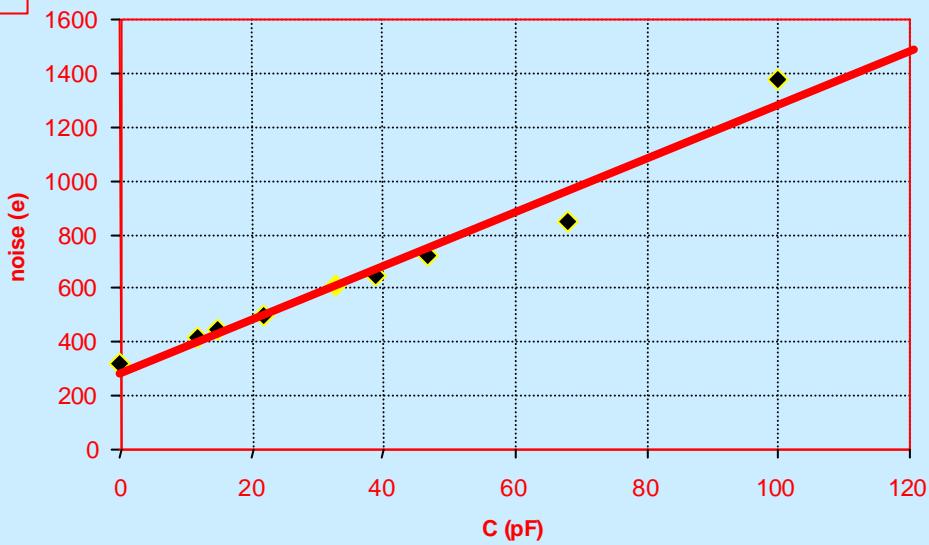
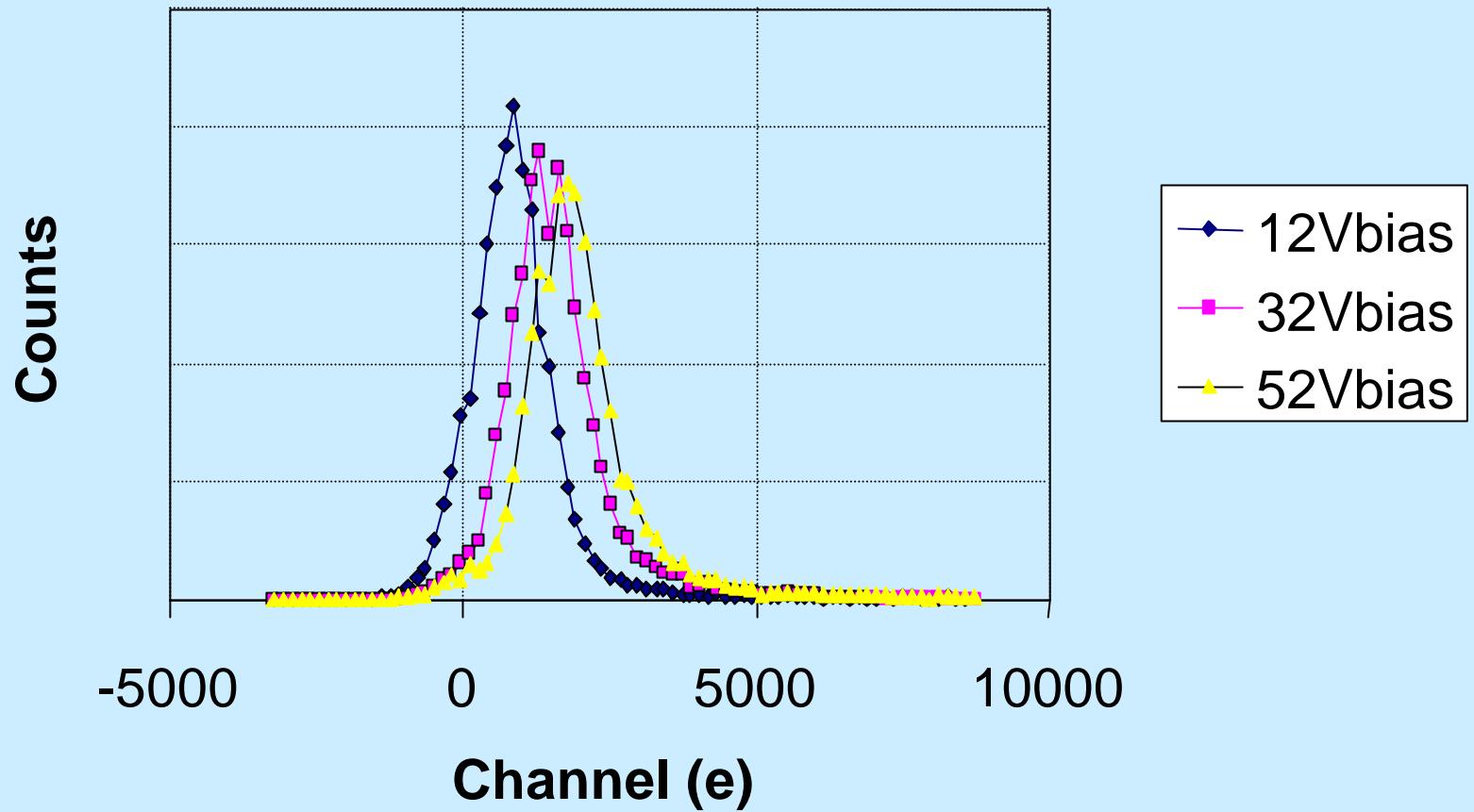


Figure of merit of the apparatus:

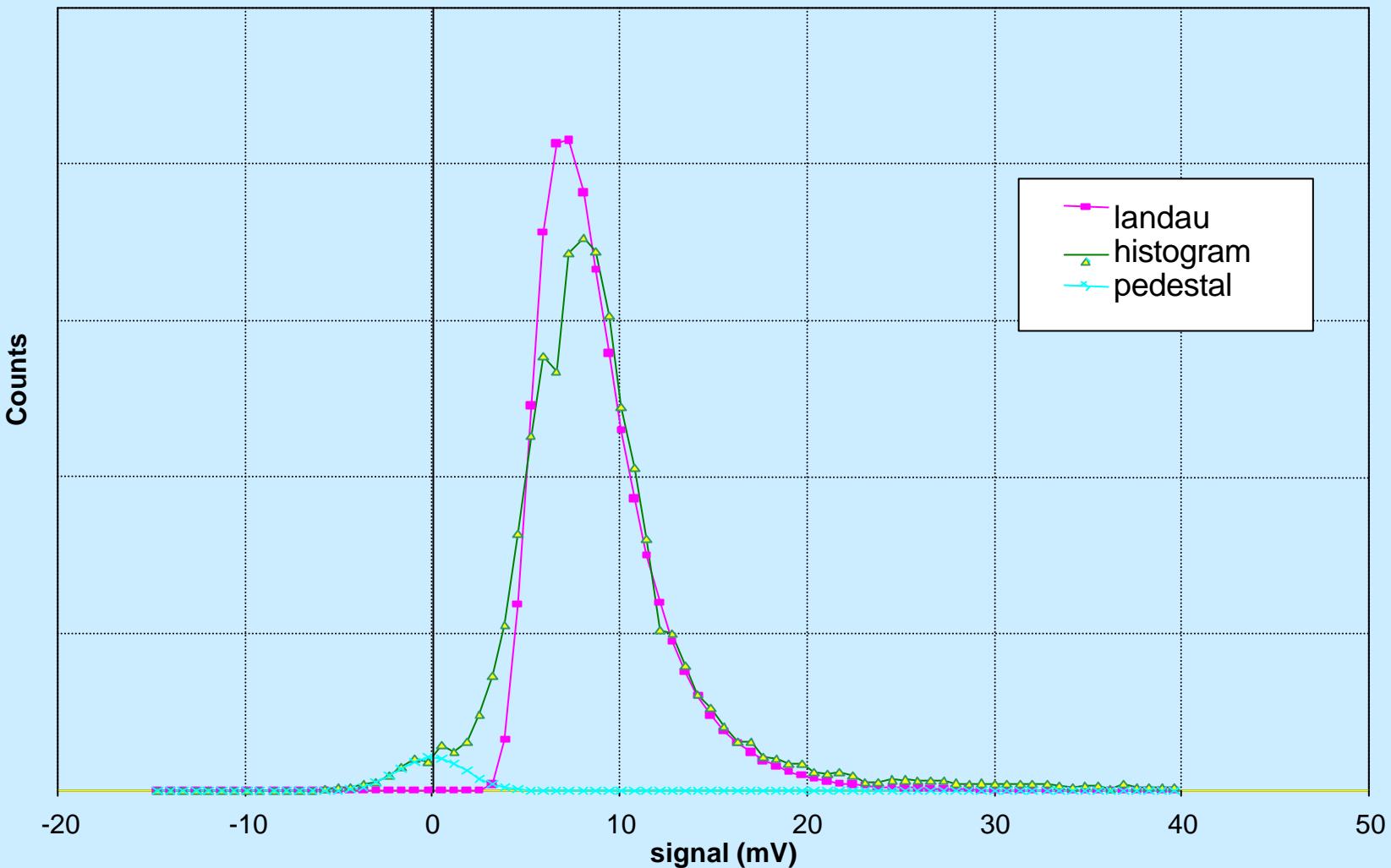
$$\text{series noise} = 300\text{e} + 10\text{e/pF}$$



PULSE HEIGHT SPECTRUM AT DIFFERENT FIELDS

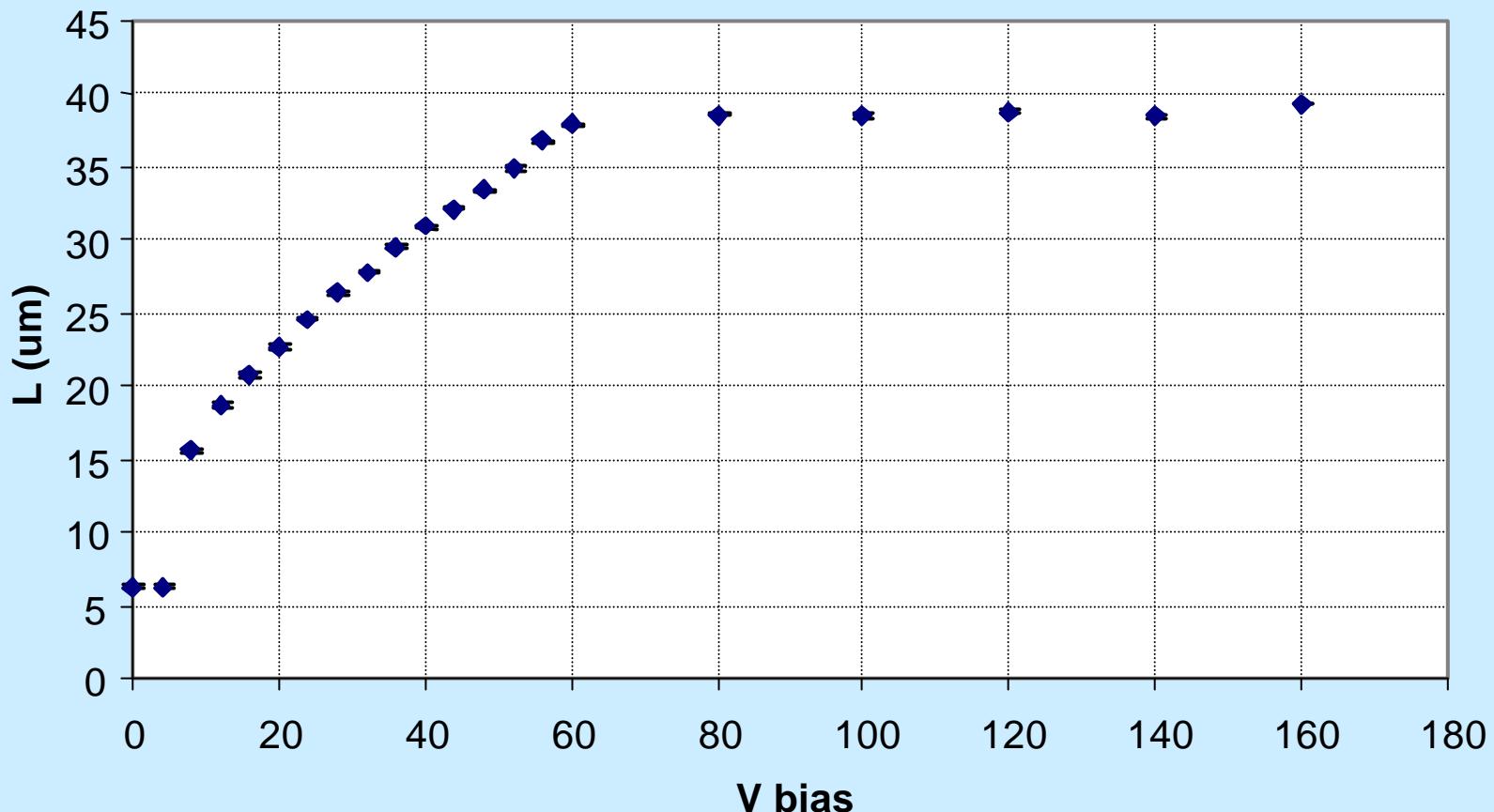


DECONVOLUTION AT SATURATION LANDAU CLEARLY SEPARATED FROM PEDESTAL



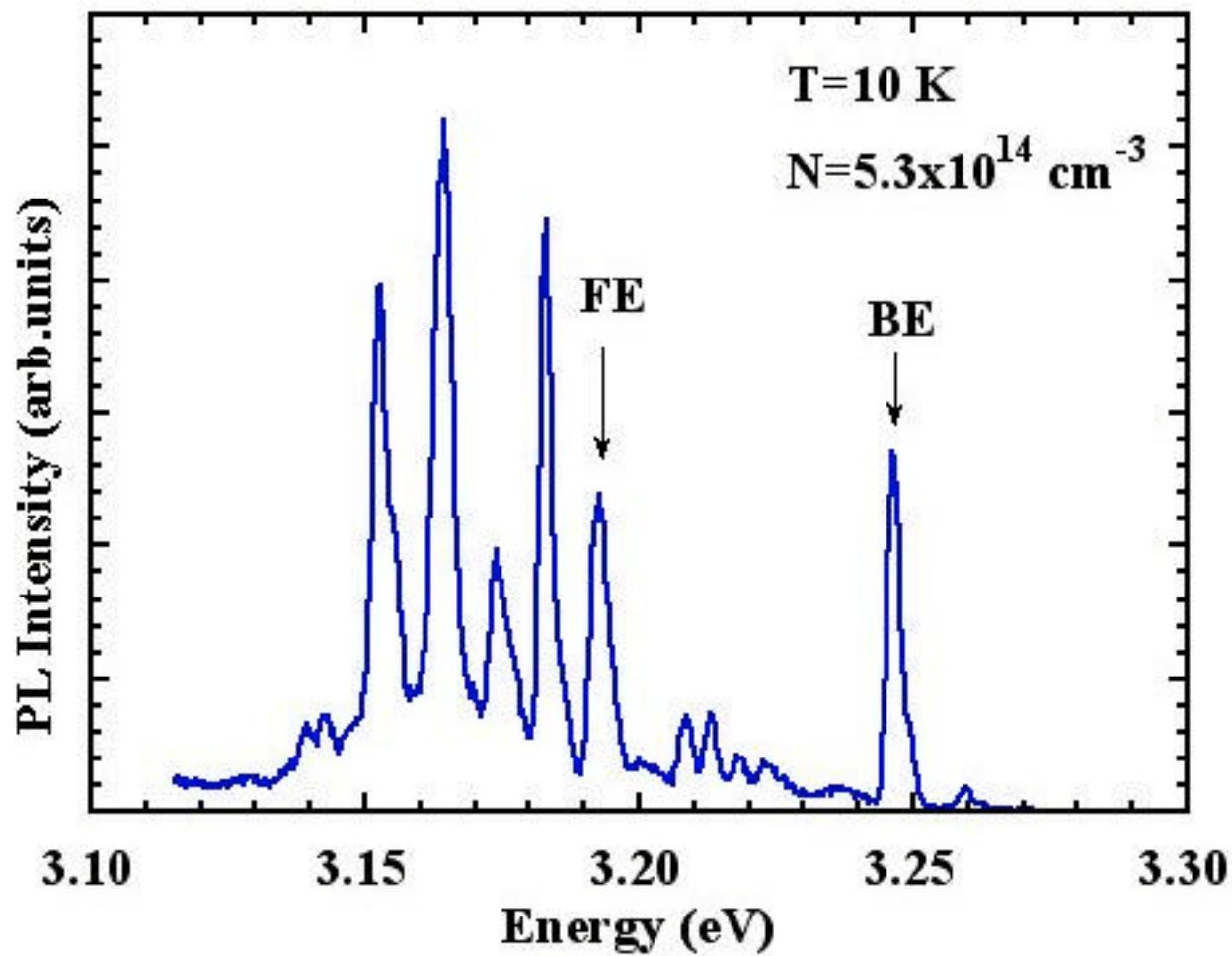
electrons/55 per mm

The cce MIP measurements are consistent with the other characterization: $V_{sat} = 60V$ $N_{eff} = 4 \cdot 10^{13}/cm^3$
100% efficiency



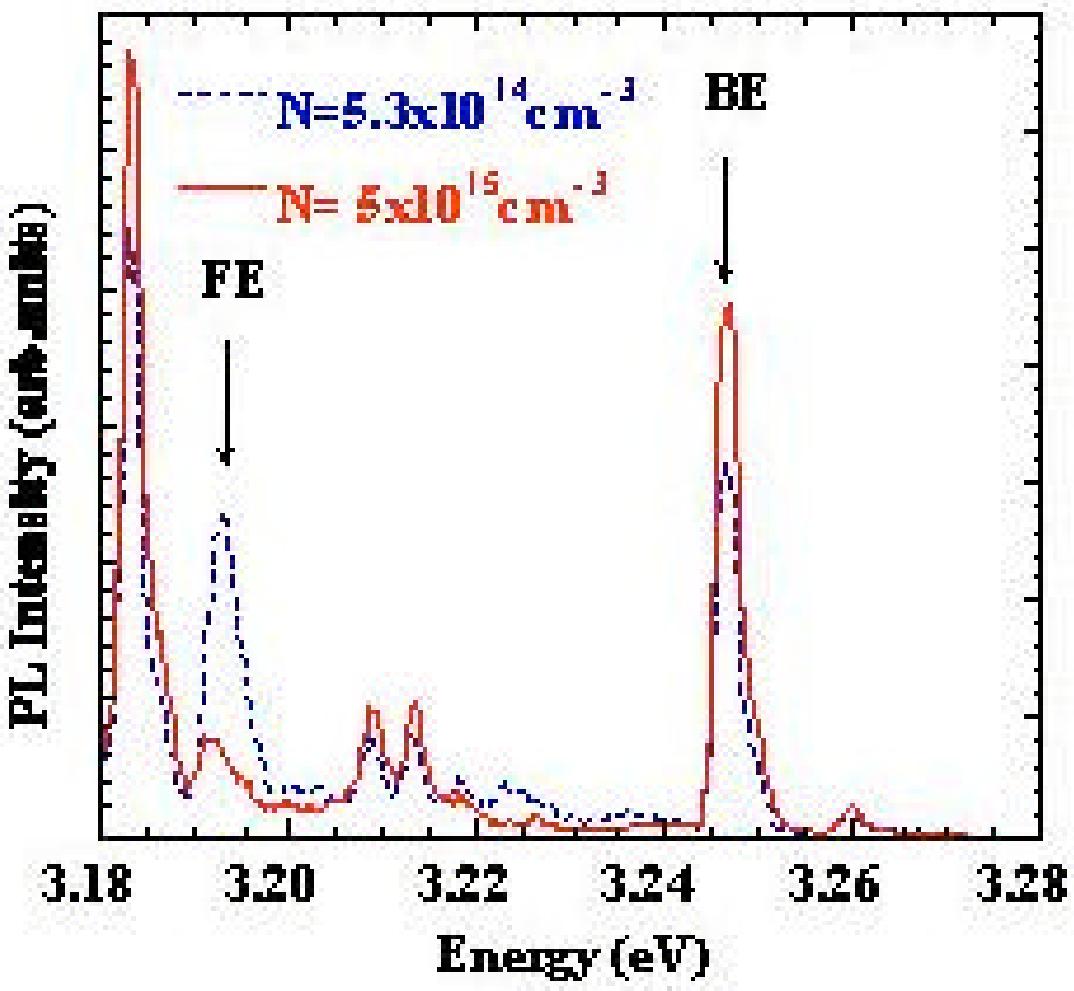
Photoluminescence measurements

- Sample excitation by means of a frequency-doubled ps dye-laser (average power at 300 nm 5 mW, rep rate 76 MHz)
- PL detection by means of a standard time-integrated photon counting

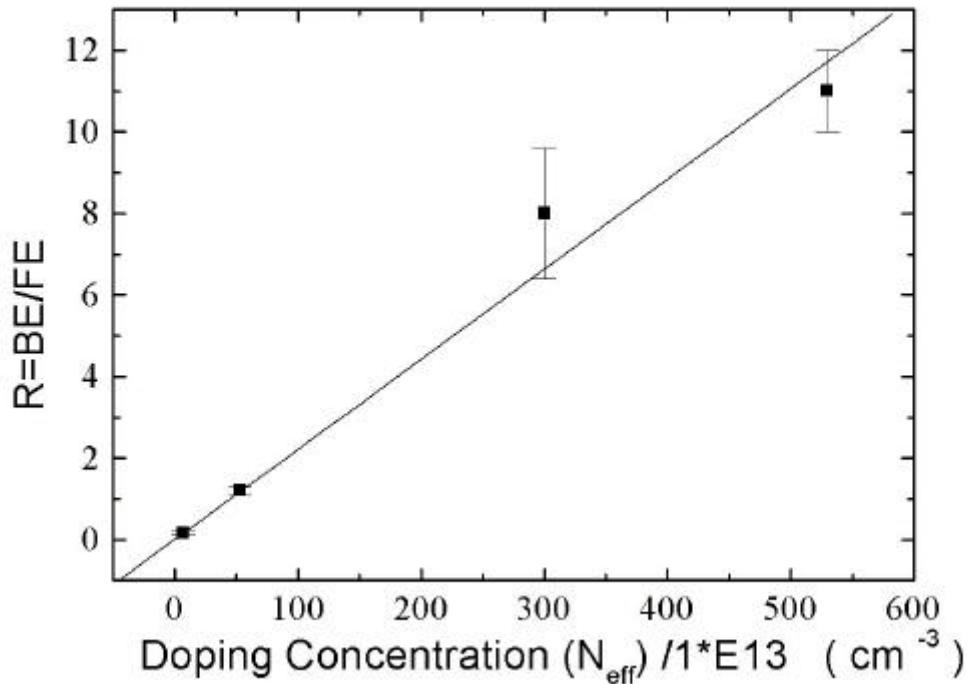


Photoluminescence main result

- Evidence of a strong correlation between the doping level and the bound (BE) and free exciton (FE) emissions.
- In particular an increase in the doping level significantly reduces the intrinsic (FE) radiative recombination.

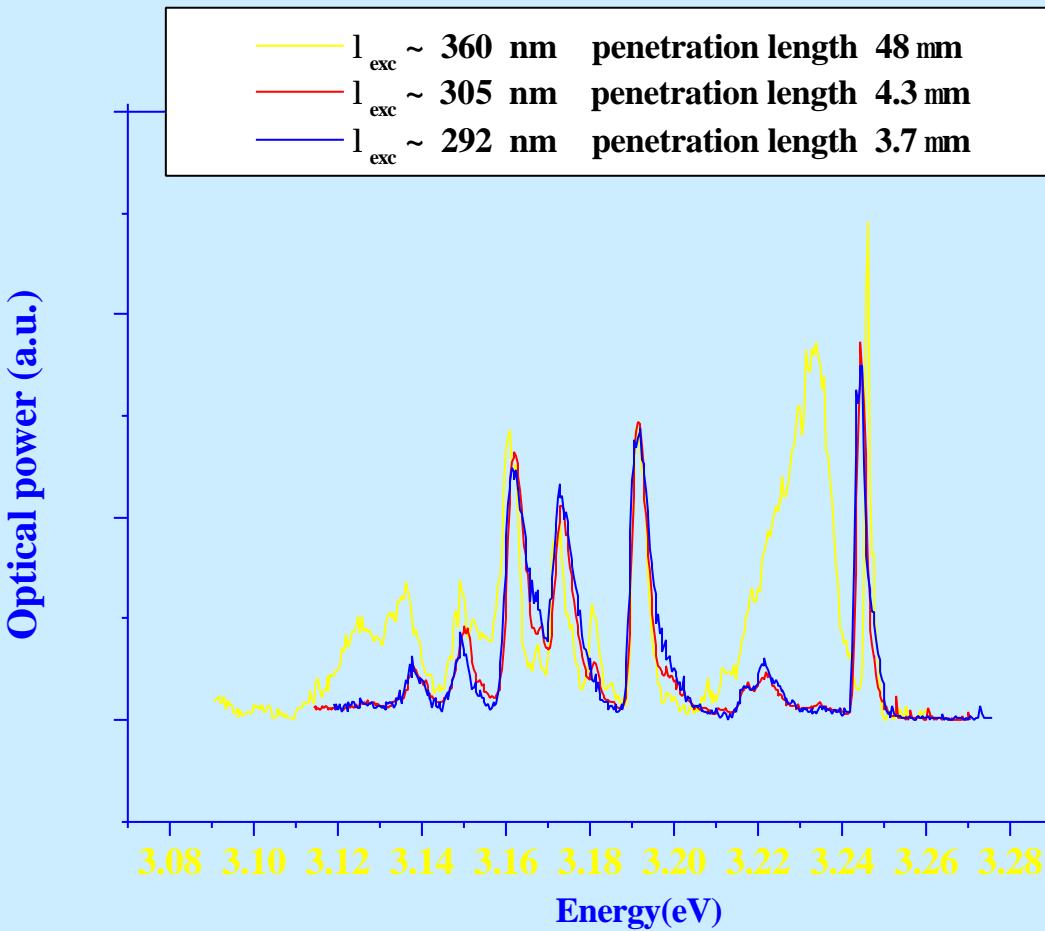


Correlation suggested by I.G. Ivanov et al. J.Appl. Phys. 80 (1990) 3504



Slope $A = 4.5 \cdot 10^{14} \text{ cm}^{-3}$ to be compared with the value reported by Ivanov ($5.2 \cdot 10^{14} \text{ cm}^{-3}$)
The difference can be ascribed to the different samples temperature in the two analyses

By tuning the excitation wavelength the penetration depth can be changed. When the probe reaches the bulk the BE feature increases and a luminescence band is strongly enhanced.



Conclusions

- IKZ compares favourably with CREE
- lower doping level, higher thickness, more reliable metallization, high diffusion length
- higher compensation introduces disuniformity in the N_{eff} profile: test with excitonic recombination are foreseen before metallization , need of a buffer layer
- Independence of temperature of the device response
- Landau MIP spectrum resolved from the pedestal

Future Plans

- Test samples of 100 μm thickness and low doping level $\sim 10^{13}/\text{cm}^3$
- Study the homogeneity with optical measurements
- Radiation hardness study, possibly increasing the sensitivity of the cce MIP measurements